

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number.

Substitute for form 1449/PTO

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Use as many sheets as necessary)

Sheet	1	of	2
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Complete if Known

Application Number	
Filing Date	
First Named Inventor	Masood Murtuza
Art Unit	
Examiner Name	
Attorney Docket Number	TI-35639

U. S. PATENT DOCUMENTS

If you need assistance in completing the form, call 1-800-PTO-9199 (1-800-786-9199) and select option 2.

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Sheet 2

of 2

NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
MAB		K. BUCHANAN, et al., "Challenges Associated with the Integration of Nano-Porous Ultra Low k CVD Films", SEMI Technical Symposium, p. 1-2, 2002	
MAB		L. PETERS, "Removing Barriers to Low-k Dielectric Adoption", http://www.reed-electronics.com/semiconductor/index.asp?layout=articlePring&... , Last Viewed 8/26/03, p.1-6	
MAB		International SeMaTech, "Benchmarking Ultra Low-K Materials: Nanoglass Shows Promise", http://www.sematech.org/public/news/stories/nanoglass.com , Last Viewed 8/26/03, p. 1-2	
MAB		"Axcelis, Dow Coming Develop Porous Ultra-Low-K Process", http://www.reed.electronics.com/electronicnews/index.asp?layout=articlePrint&... , Last Viewed 8/26/03, p. 1	
MAB		"Nanoporous Ultra-Low Dielectric Constant Materials", http://www.ncnr.nist.gov/programs/reflectometry/highlights/nano/ , Last Viewed 8/26/03, p. 1-3	

Examiner
Signature

Mark A. Barrymiller

Date
Considered

08/05/2005

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